
Surface chemical analysis — Analysis of metal oxide films by glow-discharge optical-emission spectrometry

*Analyse chimique des surfaces — Analyse de films d'oxyde de métal
par spectrométrie d'émission optique à décharge lumineuse*

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This document was prepared by Technical Committee ISO/TC 201, *Surface chemical analysis*, Subcommittee SC 8, *Glow discharge spectroscopy*.

This second edition cancels and replaces the first edition (ISO/TS 25138:2010), which has been technically revised. The main changes compared to the previous edition are as follows:

- the element Zr has been added to the Scope;
- the description of the apparatus has been modified to include spectrometers with solid-state array detectors of the types CCD and CID;
- [Clause 6](#) has been modified for more clarity, and to include the spectrometer types;
- [Clause 8](#) has been modified for more clarity, particularly in the recommendations for calibration samples.

A list of all parts in the ISO TS 25138 series can be found on the ISO website.

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